

**Notice of References Cited**

Application/Control No.

09/930,787

Applicant(s)/Patent Under  
Reexamination  
TRAN ET AL.

Examiner

Howard Weiss

Art Unit

2814

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,756,390	05-1998	Juengling et al.	438/439
	B	US-			
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	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Fazan, P.C., et al., "A High-C Capacitor (20.4.fF/um sq) with Ultrathin CVD-Ta2O5 Films Deposited on Rugged Poly-Si for High Density DRAMs", 1992, IEDM 92, pp. 263-6
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	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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